



JFW

PATENT
0941-0860P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: LEE, Hueh-Chuan et al. Conf.: 6178
Appl. No.: 10/695,739 Group: 2818
Filed: October 30, 2003 Examiner: M. H. C. Tran
For: SEMICONDUCTOR STRUCTURE WITH PARTIALLY
ETCHED GATE AND METHOD OF FABRICATING
THE SAME

LARGE ENTITY TRANSMITTAL FORM

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

November 8, 2004

Sir:

Transmitted herewith is a Reply to Restriction/Election Requirement in the above-identified application.

- The enclosed document is being transmitted via the Certificate of Mailing provisions of 37 C.F.R. § 1.8.
- Petition for _____ month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$0.00 for the extension of time.
- No fee is required.
- A check in the amount of \$0.00 is enclosed.
- Please charge Deposit Account No. 02-2448 in the amount of \$0.00. A triplicate copy of this sheet is attached.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §§1.16 or 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By Joe M. Muncy #32, 334



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KM/asc
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Attachment(s)



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REPLY TO RESTRICTION REQUIREMENT

Assistant Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

November 8, 2004

Sir:

Responsive to the Office Action dated October 7, 2004, the following election and remarks are respectfully submitted in connection with the above-identified application.

REMARKS

Claims 1-42 are now pending in the present application.

The Examiner has given the following Restriction Requirement:

Group I, claims 16-23 and 35-42, drawn to a semiconductor device; and

Group II, claims 1-15 and 24-34, drawn to a process of making a semiconductor device.

In response to this requirement, Applicants hereby elect Group I, claims 16-23 and 35-42 drawn to a semiconductor device. This election is with traverse.